Nanoscribe PPGT+ 2 Photon Direct laser Writer for real 3D Lithography

Responsible

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System description

Objectives

10x NA:0.3 scan field 1um

25x,

63x N.A. 1.4 for high resolution

Sample size:

Up to 8mm Sample height with 10x objective 0.8mm^3/ h (for shell and scaffold recipes)

Up to 4inch wafers

Various holders

Processes and resists

Standard resists (Negative tone) for Dip In :IP-Dip, IPS, IPQ

Oil Immersion

Materials allowed to be decided by LNQ Labmanagement